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(54) Title: POLYMER FOR HEAT-SENSITIVE LITHOGRAPHIC PRINTING PLATE PRECURSOR

(57) Abstract: A polymer for a heat-sensitive lithographic printing plate precursor is disclosed wherein the polymer comprises a phenolic monomeric unit of which the phenyl group is substituted by a group A characterised in that the group A comprises an imide or thioimide group and wherein the modification of the polymer increases the chemical resistance of the coating of the printing plate precursor.

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